

ABSTRACT

The ceiling surface (12b) of a chamber (12) is substantially entirely formed with a gas supply port (19).
5 Further, the gas supply port (19) has shower head (20) fitted therein. The peripheral edge of the ceiling surface (12b) has connected thereto a second side wall (12d) forming an angle greater than 90 degrees with ceiling surface (12b). Further, the side surface of a susceptor (16) is formed such
10 that it forms an angle greater than 90 degrees with a mounting surface for a wafer (W) and is substantially parallel with the second side wall (12d) of the chamber (12). Further, the susceptor (16) is disposed such that the distance (L2) between its side surface and the second side
15 wall (12d) is greater than the distance (L1) between the shower head (20) and the wafer (W).